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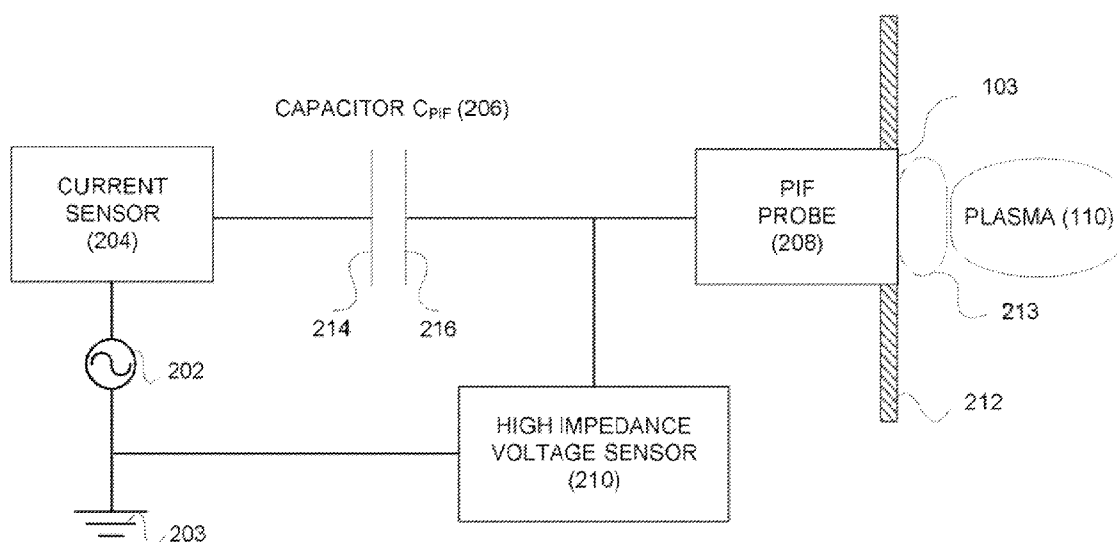
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(54) Title: CONTROLLING PLASMA PROCESSING USING PARAMETERS DERIVED THROUGH THE USE OF A PLANAR ION FLUX PROBING ARRANGEMENT



(57) Abstract: Methods and apparatus for detecting and/or deriving the absolute values of and/or the relative changes in parameters such as the plasma potential and the ion flux using a Planar Ion Flux (PIF) probing arrangement are disclosed. The detected and/or derived values are then employed to control plasma processing processes.

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